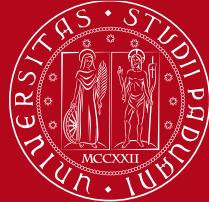


1222-2022
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DI PADOVA

Calibrazione ottica e metrologica dello spettrografo per la missione Solar-C EUVST

Gabriele Zeni - 37th Cycle

Supervisor: Dr. Lorenzo Cocola

Co-supervisor: Prof. Giampiero Naletto

Admission to second year - 05/09/2022



Solar-C_EUVST

Extreme UltraViolet High-Throughput Spectroscopic Telescope

JAXA M-class mission

International participation

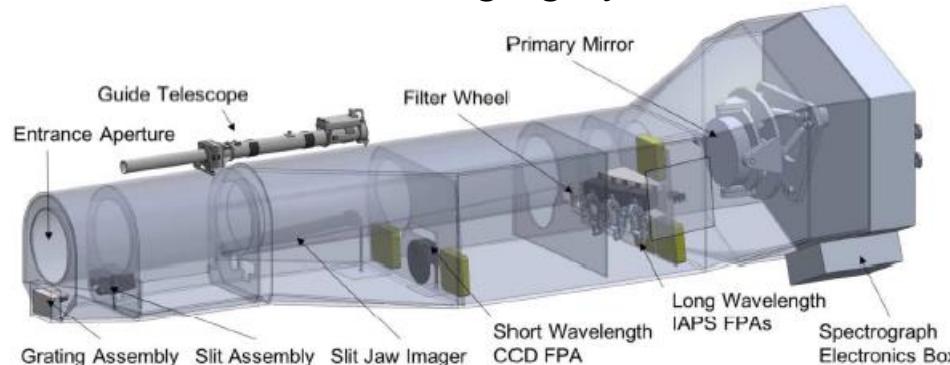
Purpose: to understand

- Formation of solar atmosphere and solar wind
- Instabilities of the solar atmosphere



Primary instrumentations:

- EUV spectrometer
- Slit-Jaw imaging system



Observe all
temperature
regimes

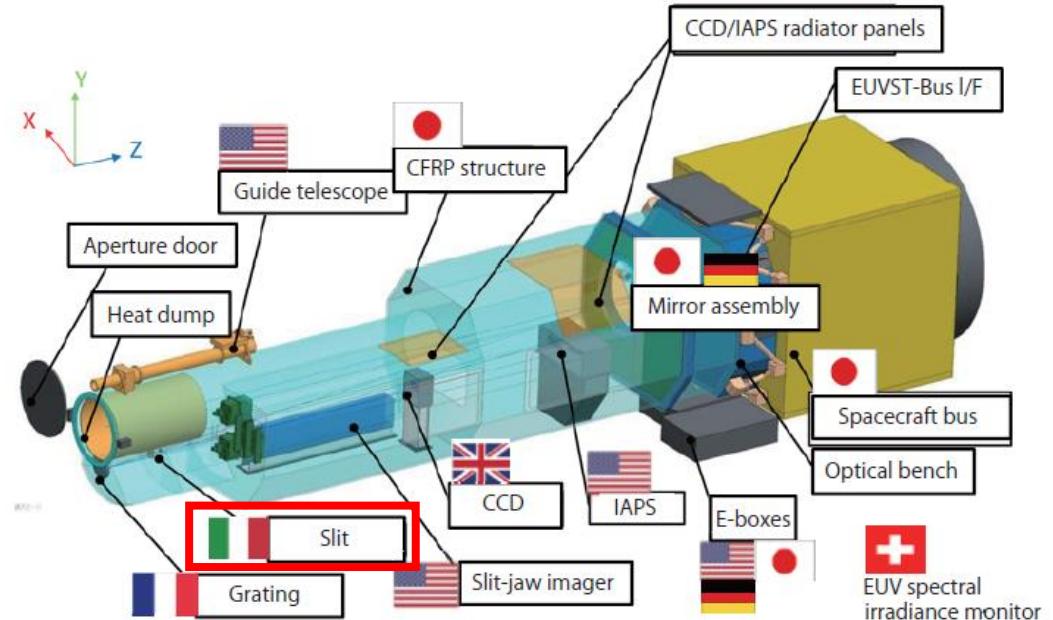
Track the evolution of the
elemental structures of the
atmosphere

Spectroscopic analysis
of the dynamics of
elementary process

The Italian contribution

INAF (Istituto Nazionale di Astrofisica) is responsible of the realization of the Slit Assembly

CNR-IFN will perform the calibration of the Slit Assembly



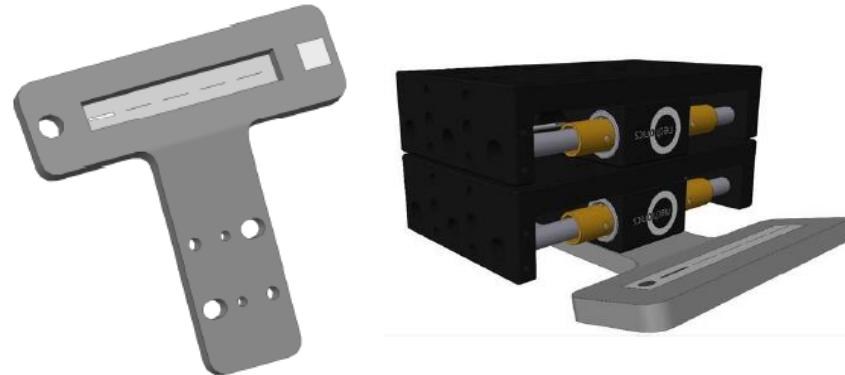


Slit Assembly

Limit the light entering the imaging spectrograph

Reflect light onto the Slit-Jaw Imager

- 4 scientific slits
- 1 calibration slit
- 1 pinhole
- 1 circular aperture
- stop position



Positioner: two linear translators (piezo-actuator)

Redundancy and efficiency



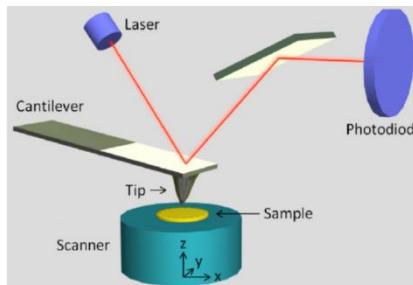
CNR-IFN has to optically and metrologically calibrate the Slit Assembly

- Preparation of the instrumentations needed to perform the measurements
- Metrological characterization of the slits and the substrate
- Morphological characterization of the slits and the substrate
- Reflectivity test of the substrate
- Calibration of the mechanism: repeatability, linearity, life test, hysteresis, characterization of the uncertainties



Metrological characterization of the slits and the substrate

AFM (Atomic Force
Microscope)



Analysis of
microroughness

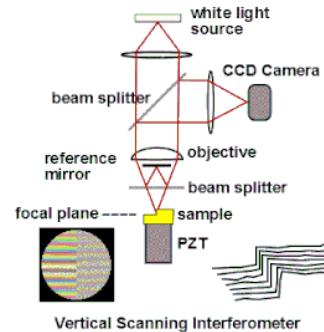
Optical microscope



Analysis of surface
roughness
Shape of the slits

Morphological characterization of the substrate

Interferometer



Analysis of substrate planarity and thermal deformation

Reflectivity test of the substrate

Reflectometer UV-vis

Reflectivity test in UV-vis band

FTIR

Reflectivity test in IR band



Research activities II

- Test of the instrumentation: sample test and broadband characterization of coatings (UV, vis, IR)
- Collaboration with the selected lab during the electron beam lithography process: slits alignment, slits shape
- Collaboration with the selected industry during the realization/testing of the Slit Assembly: calibration of the mechanism (repeatability, linearity, life test, hysteresis, characterization of the uncertainties)



Slit Assembly coating analysis

with Alain Jody Corso, Luca Poletto

Preliminary theoretical analysis of the Slit Assembly coating

High solar input on thin substrate → Coating to reduce absorption

Coating requirements:

- High reflectivity, especially in 280 nm band
- Not exceed 600 nm thickness

Coating	N7419	N7420	N7421	N7422	P3157	P3158
Solar absorbance α	0.254	0.322	0.396	0.175	0.560	0.603
Solar flux absorption by PM (W)	22.22	28.20	34.68	15.33	48.96	52.76
Reflected Solar flux (W)	65.27	59.29	52.82	72.16	38.53	34.73
Solar flux input on slit (W)	4.64	4.22	3.75	5.13	2.74	2.47

Slit Assembly coating analysis

Metal-based coating



Gold 

Silver 

Aluminum 



Needs
protective layer

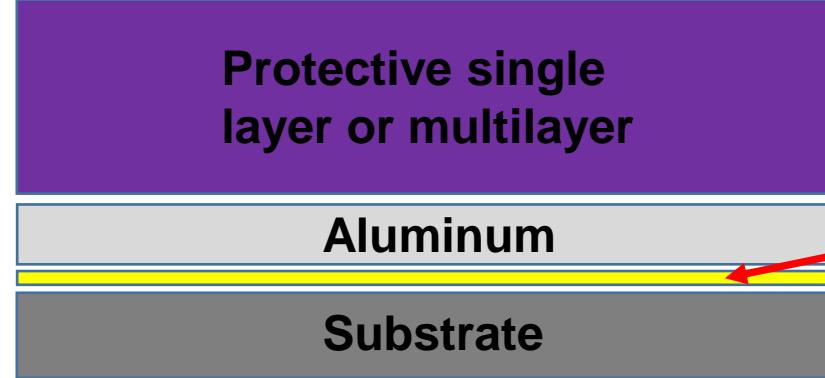
Protected Al coating

Protective single
layer or multilayer

Aluminum

Substrate

Chromium
(adhesion
layer)

- 
- Single-layer protected Al coating
 - Multilayer protected Al coating

Slit Assembly coating analysis

Single-layer protected Al coating

- Simple (single layer of SiO_2 or MgF_2)
- Not so efficient

Multilayer protected Al coating

- Complex (fully dielectric multilayer)
- Very efficient



Theoretical analysis of several coating structures:

- **SiO_2/Al and MgF_2/Al single layer**
- **$[\text{MgF}_2/\text{SiO}_2]^3/\text{Al}$; $[\text{Al}_2\text{O}_3/\text{SiO}_2]^3/\text{Al}$; $[\text{TiO}_2/\text{SiO}_2]^3/\text{Al}$ and**
- $\text{SiO}_2/[\text{ZrO}_2/\text{SiO}_2]^3/\text{Al}$ multilayer**

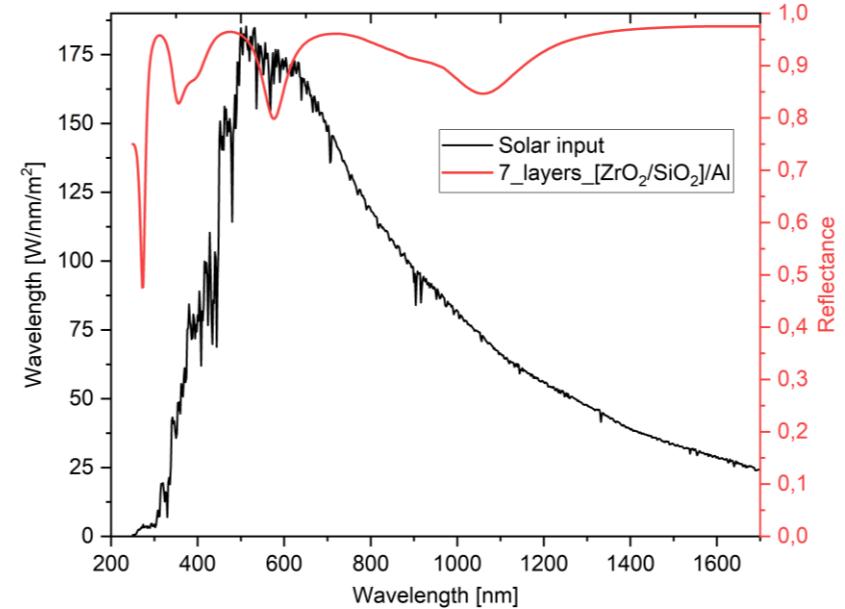
A genetic algorithm is prepared to optimize the thickness of each single layer
Another algorithm calculates the absorbed heat

N7422 Primary Mirror Coating

Slit coating	Absorbed Heat (250-1700 nm)	Reflected Heat
Bare Al (reference)	0.357 W	4.213 W
Al + single layer [SiO ₂ or MgF ₂]	0.467 W	4.103 W
[Al ₂ O ₃ /SiO ₂]/Al, 6 layers	0.386 W	4.184 W
[ZrO ₂ /SiO ₂]/Al, 7 layers	0.363 W	4.207 W

Slit Assembly coating analysis

Label	Structure	Total thickness
[ZrO ₂ /SiO ₂] / Al, 7 layers	SiO ₂ (40 nm)	523 nm
	ZrO ₂ (74 nm)	
	SiO ₂ (82 nm)	
	ZrO ₂ (25 nm)	
	SiO ₂ (32 nm)	
	ZrO ₂ (90 nm)	
	SiO ₂ (80 nm)	
	Al (90 nm)	
	Cr (10 nm) – adhesion layer	



The study has been shared with other EUVST teams and it will be presented at the ICSO 2022 conference

Next steps:

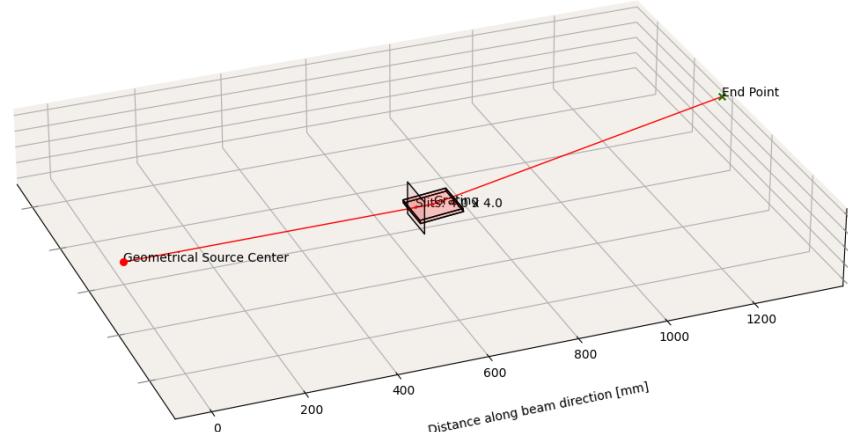
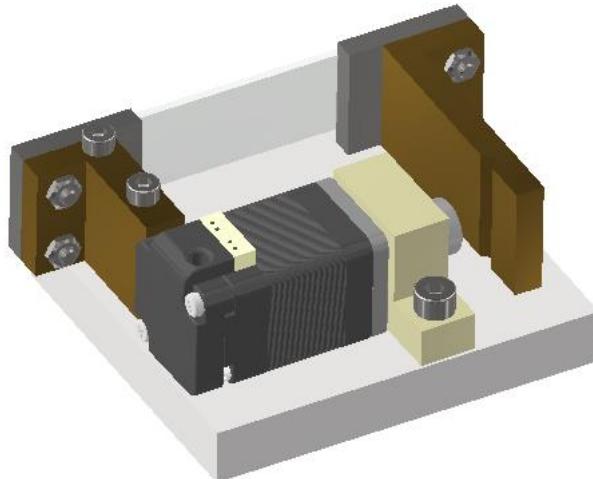
- Reflectivity test on coating samples
- Comparison between the real performance of the two multilayer $[Al_2O_3/SiO_2]^3/Al$ and $SiO_2/[ZrO_2/SiO_2]^3/Al$

XUV deformable grating

with Fabio Frassetto, Luca Poletto

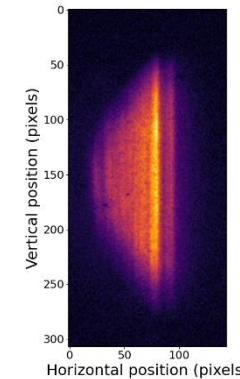
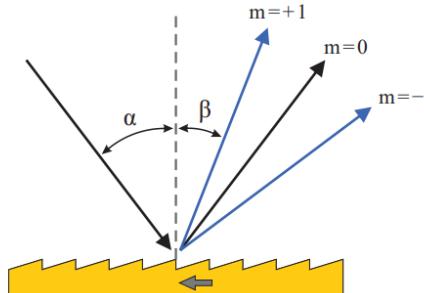
Focusing test of XUV deformable grating

Deformable grating could be used in monochromator, reducing the amount of optical elements

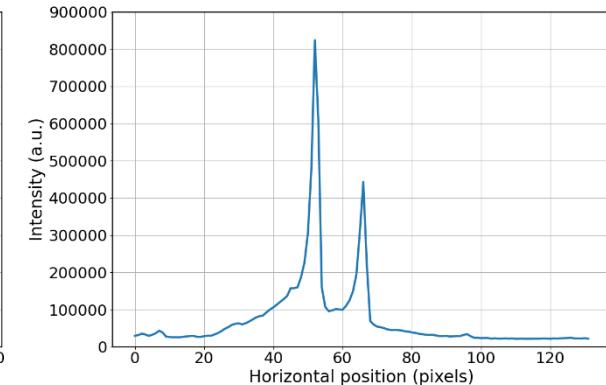
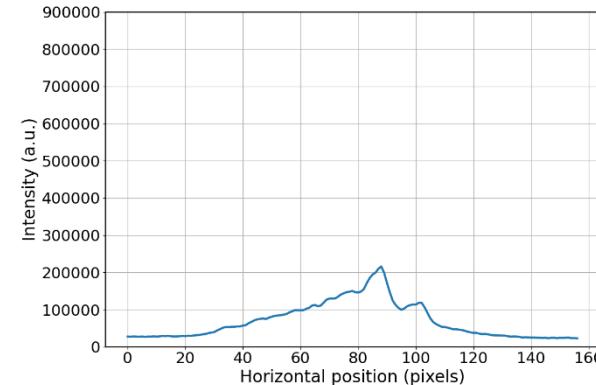
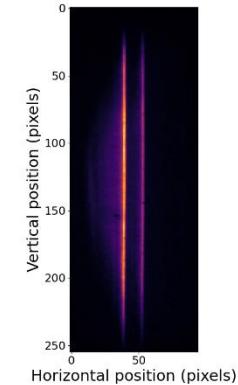


XUV deformable grating

Test with He and Ne,
three lines each, both
with the blaze arrow of
the grating toward the
source and toward the
camera



Ne 74.0 nm
doublet

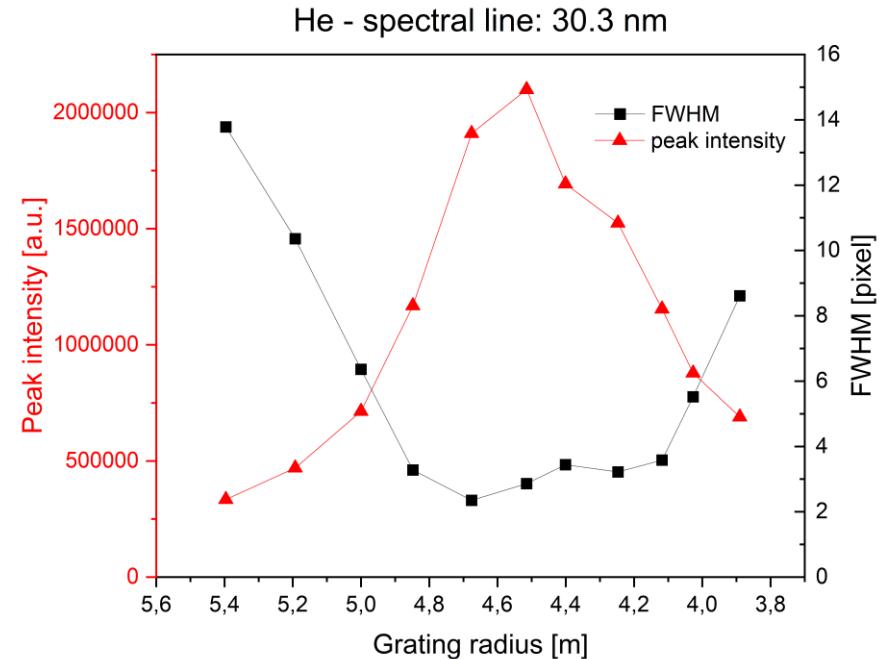


XUV deformable grating

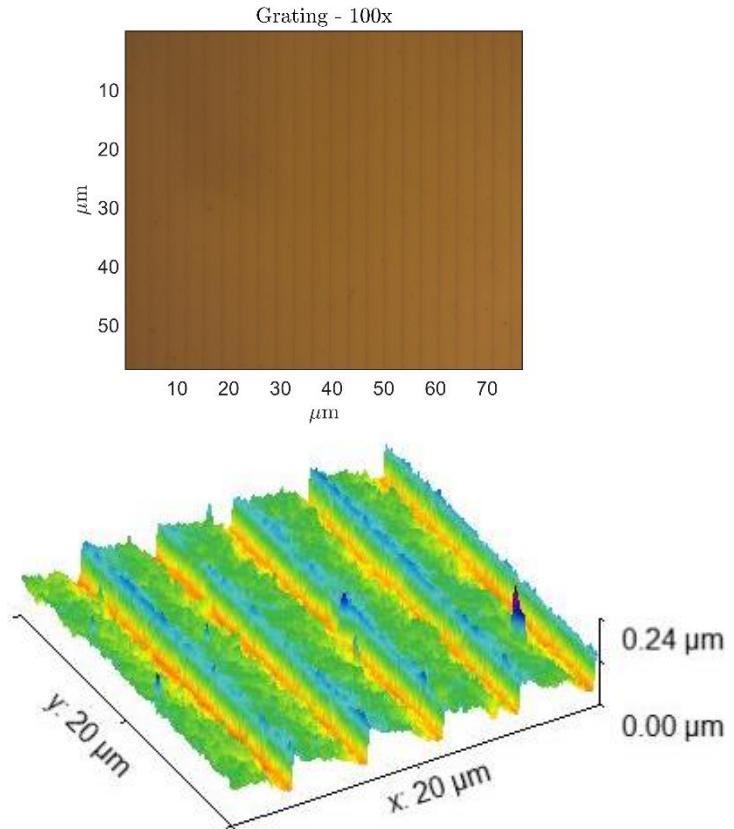
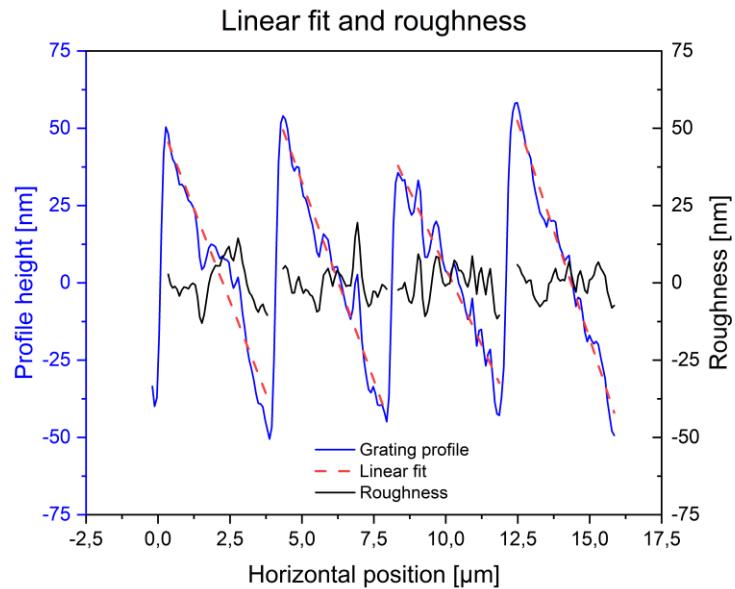
Plot the peak width and
the peak intensity



Obtain the bending
radius for the in-focus
position



Optical microscope surface analysis AFM surface and roughness analysis





Results:

- Fully working mounting frame
- Complete bending test of the deformable grating
- Complete analysis of the grating surface

Next steps:

- Paper and conference presentation
- Possible development of a complete two stage bendable grating instrumentation

Thanks for the attention

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Activities for unexpected delays

- Collaboration in research activities at CNR-IFN lab, especially characterization of optical space elements operating in the UV and visible band
- Collaboration in the research activities about deformable grating and satellite instrumentation for the EUV observation
- Study of the reflectivity of mirror coatings in the UV band